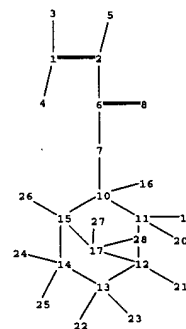
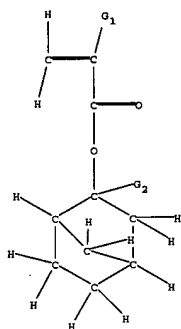


CAS Search
Updated



chain nodes :

1 2 3 4 5 6 7 8 16 19 20 21 22 23 24 25 26 27 28

ring nodes :

10 11 12 13 14 15 17

chain bonds :

1-2 1-3 1-4 2-5 2-6 6-7 6-8 7-10 10-16 11-19 11-20 12-21 13-22 13-23 14-24
14-25 15-26 17-27 17-28

ring bonds :

10-11 10-15 11-12 12-13 12-17 13-14 14-15 15-17

exact/norm bonds :

2-5 6-7 6-8 7-10 10-11 10-15 10-16 11-12 12-13 12-17 13-14 14-15 15-17

exact bonds :

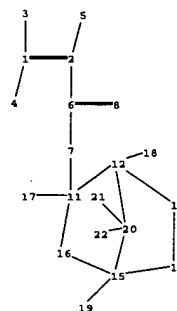
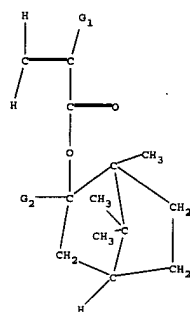
1-2 1-3 1-4 2-6 11-19 11-20 12-21 13-22 13-23 14-24 14-25 15-26 17-27 17-28

G1:H,CH3

G2:CH3,Et

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 10:CLASS 11:Atom
12:Atom 13:Atom 14:Atom 15:Atom 16:CLASS 17:Atom 19:CLASS 20:CLASS 21:CLASS
22:CLASS 23:CLASS 24:CLASS 25:CLASS 26:CLASS 27:CLASS 28:CLASS



chain nodes :

1 2 3 4 5 6 7 8 17 18 19 21 22

ring nodes :

11 12 13 14 15 16 20

chain bonds :

1-2 1-3 1-4 2-5 2-6 6-7 6-8 7-11 11-17 12-18 15-19 20-21 20-22

ring bonds :

11-12 11-16 12-13 12-20 13-14 14-15 15-16 15-20

exact/norm bonds :

2-5 6-7 6-8 7-11 11-12 11-16 11-17 12-13 12-20 13-14 14-15 15-16 15-20

exact bonds :

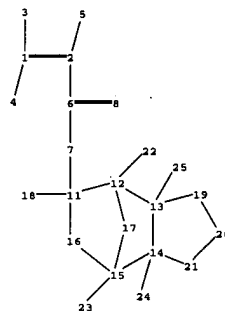
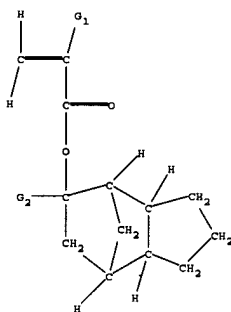
1-2 1-3 1-4 2-6 12-18 15-19 20-21 20-22

G1:H,CH3

G2:CH2,Et

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 11:Atom 12:Atom
13:Atom 14:Atom 15:Atom 16:Atom 17:CLASS 18:CLASS 19:CLASS 20:Atom 21:CLASS
22:CLASS



chain nodes :

1 2 3 4 5 6 7 8 18 22 23 24 25

ring nodes :

11 12 13 14 15 16 17 19 20 21

chain bonds :

1-2 1-3 1-4 2-5 2-6 6-7 6-8 7-11 11-18 12-22 13-25 14-24 15-23

ring bonds :

11-12 11-16 12-13 12-17 13-14 13-19 14-15 14-21 15-16 15-17 19-20 20-21

exact/norm bonds :

2-5 6-7 6-8 7-11 11-12 11-16 11-18 12-13 12-17 13-14 13-19 14-15 14-21 15-16
15-17 19-20 20-21

exact bonds :

1-2 1-3 1-4 2-6 12-22 13-25 14-24 15-23

G1:H,CH3

G2:CH2,Et

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 11:Atom 12:Atom
13:Atom 14:Atom 15:Atom 16:Atom 17:Atom 18:CLASS 19:Atom 20:Atom 21:Atom 22:CLASS
23:CLASS 24:CLASS 25:CLASS

=> d his

(FILE 'HOME' ENTERED AT 17:51:00 ON 11 SEP 2003)

FILE 'REGISTRY' ENTERED AT 17:51:06 ON 11 SEP 2003

L1 SCREEN 964 AND 970 AND 2067
L2 SCREEN 1821 OR 1822 OR 1823 OR 1824
L3 STRUCTURE UPLOADED
L4 QUE L3 AND L1 AND L2
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 SCREEN 970 AND 2067
L9 STRUCTURE UPLOADED
L10 QUE L9 AND L8
L11 0 S L4 SSS SAM
L12 6 S L7 SSS SAM
L13 7 S L10 SSS SAM
L14 22303 S 108-31-6/CRN

FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 17:53:42 ON 11 SEP 2003

L15 69219 S L12 OR L13 OR L14
L16 18 S L11 OR L12 OR L13
L17 14 S L16 AND L14
L18 9 DUPLICATE REMOVE L17 (5 DUPLICATES REMOVED)

=> d l18 1-9 ibib

L18 ANSWER 1 OF 9 USPATFULL on STN

ACCESSION NUMBER: 2003:81787 USPATFULL
TITLE: Polymer with a pericyclic protective group and resist
composition containing the same
INVENTOR(S): Chang, Sheng-Yueh, Taipei Hsien, TAIWAN, PROVINCE OF
CHINA
Ho, Bang-Chein, Hsinchu, TAIWAN, PROVINCE OF CHINA
Chang, Jui-Fa, Hsinchu, TAIWAN, PROVINCE OF CHINA
Chen, Jian-Hong, Hsinchu, TAIWAN, PROVINCE OF CHINA
Tai, Ming-Chia, Keelung, TAIWAN, PROVINCE OF CHINA
PATENT ASSIGNEE(S): Industrial Technology Research Institute, Hsinchu,
TAIWAN, PROVINCE OF CHINA (non-U.S. corporation)
Everlight Chemical Industrial Corporation, Taipei,
TAIWAN, PROVINCE OF CHINA (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6538086	B1	20030325
APPLICATION INFO.:	US 2000-514921		20000228 (9)
DOCUMENT TYPE:	Utility		
FILE SEGMENT:	GRANTED		
PRIMARY EXAMINER:	Ashton, Rosemary		
LEGAL REPRESENTATIVE:	Darby & Darby		
NUMBER OF CLAIMS:	2		
EXEMPLARY CLAIM:	1		
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)		
LINE COUNT:	364		

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L18 ANSWER 2 OF 9 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2002:272837 CAPLUS
DOCUMENT NUMBER: 136:310309
TITLE: Polymers with cyclopentane rings in or adjacent to the
chains, resist composition and patterning process
INVENTOR(S): Nishi, Tsunehiro; Nakashima, Mutsuo; Hasegawa, Koji;
Tachibana, Seiichiro; Kinsho, Takeshi; Watanabe,
Takeru; Hatakeyama, Jun
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 47 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1195390	A1	20020410	EP 2001-307791	20010913
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2002161116	A2	20020604	JP 2001-269745	20010906

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 10014493	A1	20010906	DE 2000-10014493	20000323
US 6538086	B1	20030325	US 2000-514921	20000228
FR 2805541	A1	20010831	FR 2000-5582	20000502
JP 2001342218	A2	20011211	JP 2000-158742	20000529
PRIORITY APPLN. INFO.:			US 2000-514921	A 20000228
REFERENCE COUNT:	7	THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT		

L18 ANSWER 6 OF 9 USPATFULL on STN

ACCESSION NUMBER: 2001:196771 USPATFULL
TITLE: Ester compounds, polymers, resist compositions and
patterning process
INVENTOR(S): Kinsho, Takeshi, Nakakubiki-gun, Japan
Nishi, Tsunehiro, Nakakubiki-gun, Japan
Kurihara, Hideshi, Usui-gun, Japan
Hasegawa, Koji, Nakakubiki-gun, Japan
Watanabe, Takeru, Nakakubiki-gun, Japan
Watanabe, Osamu, Nakakubiki-gun, Japan
Nakashima, Mutsuo, Nakakubiki-gun, Japan
Takeda, Takanobu, Nakakubiki-gun, Japan
Hatakeyama, Jun, Nakakubiki-gun, Japan
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S.
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6312867	B1	20011106
APPLICATION INFO.:	US 1999-431139		19991101 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1998-312533	19981102
	JP 1999-75355	19990319
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Ashton, Rosemary E.	
LEGAL REPRESENTATIVE:	Millen, White, Zelano & Branigan, P.C.	
NUMBER OF CLAIMS:	17	
EXEMPLARY CLAIM:	4	
LINE COUNT:	2117	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L18 ANSWER 7 OF 9 USPATFULL on STN

ACCESSION NUMBER: 2001:147641 USPATFULL
TITLE: Ester compounds, polymers, resist compositions and
patterning process
INVENTOR(S): Kinsho, Takeshi, Nakakubiki-gun, Japan
Nishi, Tsunehiro, Nakakubiki-gun, Japan
Kurihara, Hideshi, Usui-gun, Japan
Nakashima, Mutsuo, Nakakubiki-gun, Japan
Hasegawa, Koji, Nakakubiki-gun, Japan
Watanabe, Takeru, Nakakubiki-gun, Japan
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S.
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6284429	B1	20010904
APPLICATION INFO.:	US 2000-512108		20000224 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-47406	19990225
	JP 1999-174945	19990622
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Ashton, Rosemary E.	
LEGAL REPRESENTATIVE:	Millen, White, Zelano & Branigan, P.C	
NUMBER OF CLAIMS:	19	
EXEMPLARY CLAIM:	1	
LINE COUNT:	2016	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L18 ANSWER 8 OF 9 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 4

ACCESSION NUMBER: 2000:608477 CAPLUS
DOCUMENT NUMBER: 133:215453
TITLE: Novel ester compounds, polymers, resist compositions
and patterning process
INVENTOR(S): Kinsho, Takeshi; Nishi, Tsunehiro; Kurihara, Hideshi;
Nakashima, Mutsuo; Hasegawa, Koji; Watanabe, Takeru
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 71 pp.
CODEN: EPXXDW
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1031879	A1	20000830	EP 2000-301523	20000225
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2000309611	A2	20001107	JP 1999-174945	19990622
KR 2000058167	A	20000925	KR 2000-8963	20000224
US 6284429	B1	20010904	US 2000-512108	20000224
PRIORITY APPLN. INFO.:			JP 1999-47406	A 19990225
			JP 1999-174945	A 19990622
REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT				

L18 ANSWER 9 OF 9 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 5
 ACCESSION NUMBER: 2000:367047 CAPLUS
 DOCUMENT NUMBER: 133:18002
 TITLE: Ester monomers, polymers, resist compositions and patterning process
 INVENTOR(S): Kinsho, Takeshi; Nishi, Tsunehiro; Kurihara, Hideshi; Hasegawa, Koji; Watanabe, Takeru; Watanabe, Osamu; Nakashima, Mutsuo; Takeda, Takanobu; Hatakeyama, Jun
 PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Japan
 SOURCE: Eur. Pat. Appl., 65 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1004568	A2	20000531	EP 1999-308687	19991102
EP 1004568	A3	20010228		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2000336121	A2	20001205	JP 1999-307148	19991028
KR 2000035130	A	20000626	KR 1999-47904	19991101
US 6312867	B1	20011106	US 1999-431139	19991101
PRIORITY APPLN. INFO.:			JP 1998-312533	A 19981102
			JP 1999-75355	A 19990319